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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Smith, et al.

Docket No: TI-25250

Serial No: 09/199,829

Conf. No: 4119

Examiner: Julio Maldonado

Art Unit: 2823

Filed: 11/25/98

For: HYDROGEN PLASMA PHOTORESIST STRIP AND POLYMERIC RESIDUE
CLEANUP PROCESS FOR OXYGEN-SENSITIVE MATERIALS



EXTENSION OF TIME

Assistant Commissioner For Patents
Washington, DC 20231

MAILING CERTIFICATE UNDER 37 C.F.R. §1.8(a)

I hereby certify that the above correspondence is being deposited with the U.S. Postal Service with sufficient postage as First Class Mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, DC 20231 on 3-13-02.

Ann Trent
Ann Trent

Dear Sir:

Pursuant to 37 CFR 1.136(a), Applicants respectfully petition the Commissioner for an extension of the shortened statutory period for response in the above identified Application.

The fee for this extension is indicated below:

X One Month (\$110)

___ Three Months (\$890)

___ Two Months (\$390)

___ Four Months (\$1,390)

Any further necessary extension of time is hereby requested. Charge any and all fees, or credit any overpayment, to the deposit account of Texas Instruments Incorporated, Account No. 20-0668. **This form is submitted in duplicate.**

03/27/2002 SDENBOB1 00000001 200668 09199829
01 FC:115 110.00 CH

Respectfully submitted,

Peter K. McLarty
Agent for Applicants
Reg. No. 44,923

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